

Supporting Information

Chiral Nanoporous Structures Fabricated via Plasmon-Induced Dealloying of Au-Ag Alloy Thin Films

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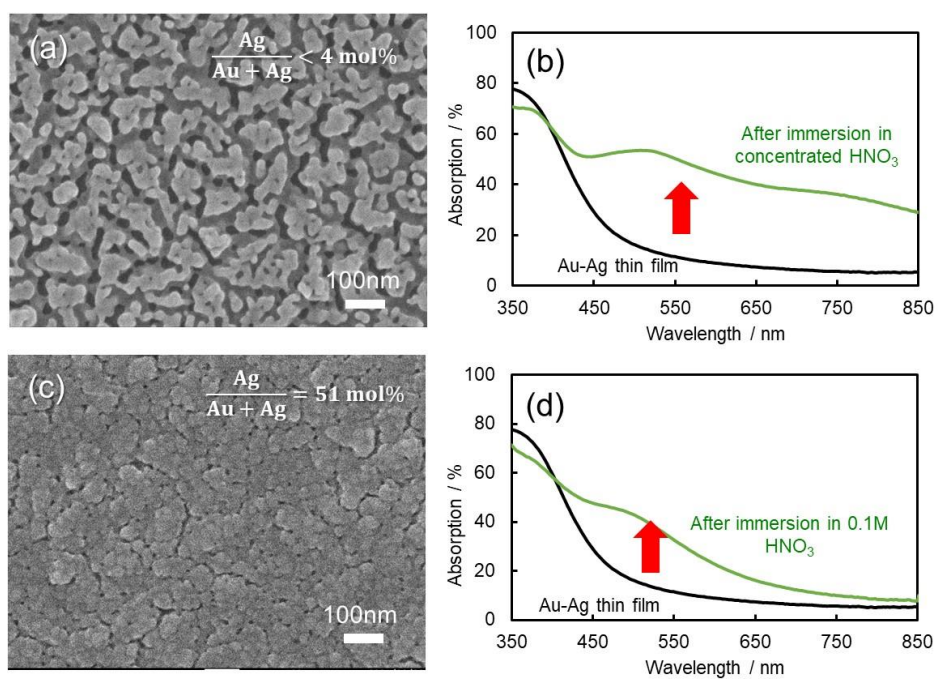


Figure S1. (a, c) SEM images and (b, d) absorption spectra of the Au-Ag thin film after chemical dealloying in (a, b) concentrated HNO_3 and (c, d) 0.1 M HNO_3 .

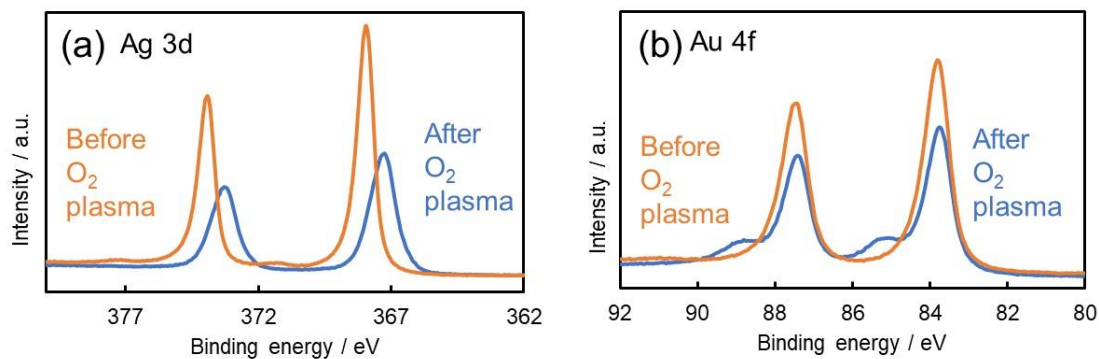


Figure S2. (a) Ag 3d and (b) Au 4f XPS spectra of the Au-Ag thin film before and after the O₂ plasma treatment (Ag: 368.2 eV, Ag₂O: 367.8 eV,^{S1} Au: 84.0 eV, Au³⁺: 85.8 eV^{S2}).

References

- S1. N. J. Firet, M. A. Blommaert, T. Burdyny, A. Venugopal, D. Bohra, A. Longo, and W. A. Smith, *J. Mater. Chem. A*, **7**, 2597 (2019).
- S2. L. K. Ono and B. R. Cuenya, *J. Phys. Chem. C*, **112**, 4676 (2008).